The 8th International Conference on Microelectronics and Plasma Technology | The 9th International Symposium on Functional Materials

Joint International Conference on The 8th ICMAP & The 9th ISFM

January 17-20, 2021 | Online Conference

[TB2] Plasma Sources and Technology II	
Date / Time	January 19 (Tue.), 2021 / 13:00-14:00
Place	Channel B
Session Chair(s)	Julian Schulze (Ruhr-Univ. Bochum, Germany)

[TB2-1] 13:00-13:20

Characteristics of Plasma Density Distribution in Focus Ring Region of VHF Narrow Gap CCP Etching Reactor

Sung Hyun Son¹, Jaemin Song¹, Haneul Lee¹, Gon-Ho Kim¹, Dae Chul Kim², and Jongsik Kim² ¹Seoul Nat'l Univ., Korea, ²KFE, Korea

[TB2-2] 13:20-13:40

A Segmented Dielectric Window Inductively Coupled Plasma Source: Comparison with a Conventional Single Dielectric ICP Source

Ju-Hong Cha, Sang-Woo Kim, Min-Seok Jang, Jee-Hun Jeong, Koon Ho Kim, and Ho-Jun Lee *Pusan Nat'l Univ., Korea*

[TB2-3] 13:40-14:00

A Comprehensive Understanding of the Ignition Process of a Pulsed Capacitively Coupled Radio Frequency Discharge:

the Effect of Power-off Duration

Xiang-Yu Wang, Yong Xin Liu, Jia Rui Liu, Quan-Zhi Zhang, and You-Nian Wang Dalian Univ., of Tech., China